

[SUBSTRATE EXPOSURE APPARATUS AND METHOD]

Abstract

A substrate exposure apparatus, having a line light source and a control system. The line light source has several point light sources. The control system converts the pattern into a timing signal to control the light status and dark status of each point light source. The control system also controls a scan light source to radiate the photoresist on the substrate, so that the photoresist is exposed. Further, in a substrate exposure method, multiple point light sources are arranged as at least one line light source to scan the photoresist once or several times to obtain a better resolution of the pattern transferred to the photoresist.